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Date Submitted: October 17, 2005

(use as many sheets as necessary)

Sheet 1 of 1

Complete if Known / ううう 4				
Application Number	Unassigned			
Filing Date	10/17/2005			
First Named Inventor	Tadahiro OHMI			
Group Art Unit	Unassigned			
Examiner Name	Unassigned			
Attorney Docket Number	039262-0143			

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	U.S. Patent Document			Date of Publication of	Pages, Columns, Lines, Where Relevant
		Number	Kind Code ² (if known)	Name of Patentee or Applicant of Cited Document	Cited Document MM-DD-YYYY	Passages or Relevant Figures Appear
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Examiner Initials*	Cite No.1	Offic	Foreign Patent Do	ocument Kind Code ⁵ (if known)	Name of Patentee or Applicant of Cited Documents	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
/1.1./	A2	JP	2002-343961	Α	SONY CORP.	11-29-2002		
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· ·		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ⁶
/T.T./	A4	M. SATO et al., "Rapid Oxidation of SiC Using Microwave-Discharged 02 Plasma at Low Temperatures (<300°C)," Jap. J. of Applied Physics, Part 2, March 1, 2002, Vol. 41:3A, pp. L233-L235.	
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Examiner Signature /Thien Tran/ Date Cons	10/23/2008 dered
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